

REMARKS

In reply to the Office Action of February 24, 2004, Applicant submits the following remarks. Claims 19, 21, 27 and 29 have been amended. Claim 28 has been cancelled. Claim 43 is new. No new matter has been added. Claims 19-27 and 29-43 are now pending after entry of this amendment. The applicant respectfully requests reconsideration in view of the foregoing amendments and these remarks.

I. Objections to the Drawings

Formal drawings are submitted with this response. The applicant has corrected the items that were objected to and believes that the drawings are now in proper form.

II. Objections to the Specification

The applicant has corrected the informalities in the specification and amended the title. The applicant believes these amendments address the Examiner's concerns.

III. Section 102 Rejections

Claim 19 was rejected under 35 U.S.C. 102(b) as allegedly being anticipated by JP 2,046,407 ("Koji"). The applicant respectfully disagrees.

Amended claim 19 recites a method of producing laterally integrated semiconductor components. A mask is layered over a semiconductor component on an epitaxial substrate, the mask defining one or more windows to the substrate. The mask layer is removed by introducing at least one fluoride based compound into an epitaxy reactor.

Koji describes forming a silicon dioxide film on a zinc sulfide layer (Abstract, line 1-3). The silicon dioxide film is subsequently removed with HF (Abstract, lines 11-12).

Koji states that an optical waveguide is completed by removing silicon dioxide. However, in the abstract, Koji does not teach or describe removing a masking layer by introducing a fluoride based compound into an epitaxy reactor. The applicant therefore submits that claim 19 is not anticipated by the Koji abstract.

While no rejection was specifically articulated, the applicant believes that claims 20-30 were rejected for substantially the same reason as provided for claim 19. Claims 20-30 depend

directly or indirectly from claim 19. The applicant submits that the Koji abstract does not anticipate claims 20-30 for at least the reasons stated above with respect to claim 19.

IV. New Claim

Claim 43 has been added. Claim 43 depends from claim 19 and includes an additional limitation of cooling the epitaxy reactor walls prior removing the mask layer. Epitaxy reactors can have quartz windows. The fluoride based compounds that are used for removing the mask layer, as required by claim 19, react with quartz. To protect the reactor walls, the walls are cooled, which decreases the reactivity of the quartz with the fluoride based compounds. The Koji abstract does not teach or suggest removing a masking layer by introducing a fluoride based compound into an epitaxy reactor, much less cooling epitaxy reactor walls prior to removing the masking layer. For at least this reason, the applicant submits that claim 43 is not anticipated by the Koji abstract.

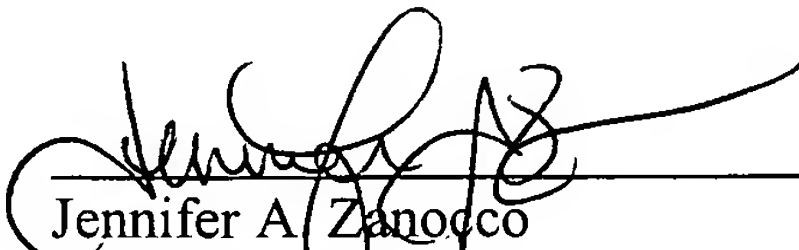
IV. Allowed Claims

The applicant thanks the Examiner for allowing claims 31-42.

No fee is believed to be due. If, however, there are any charges or credits, please apply them to deposit account 06-1050.

Respectfully submitted,

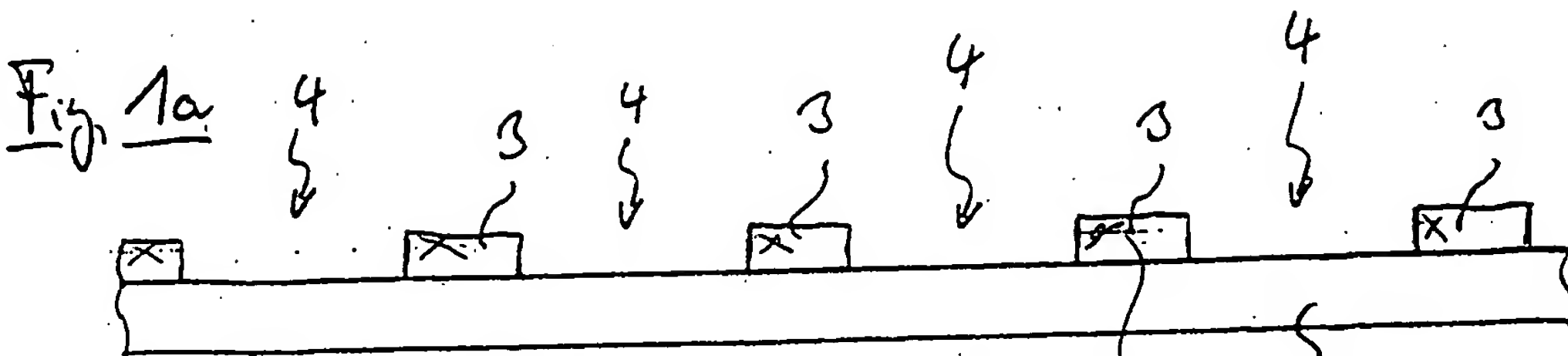
Date: May 24, 2004



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1/5



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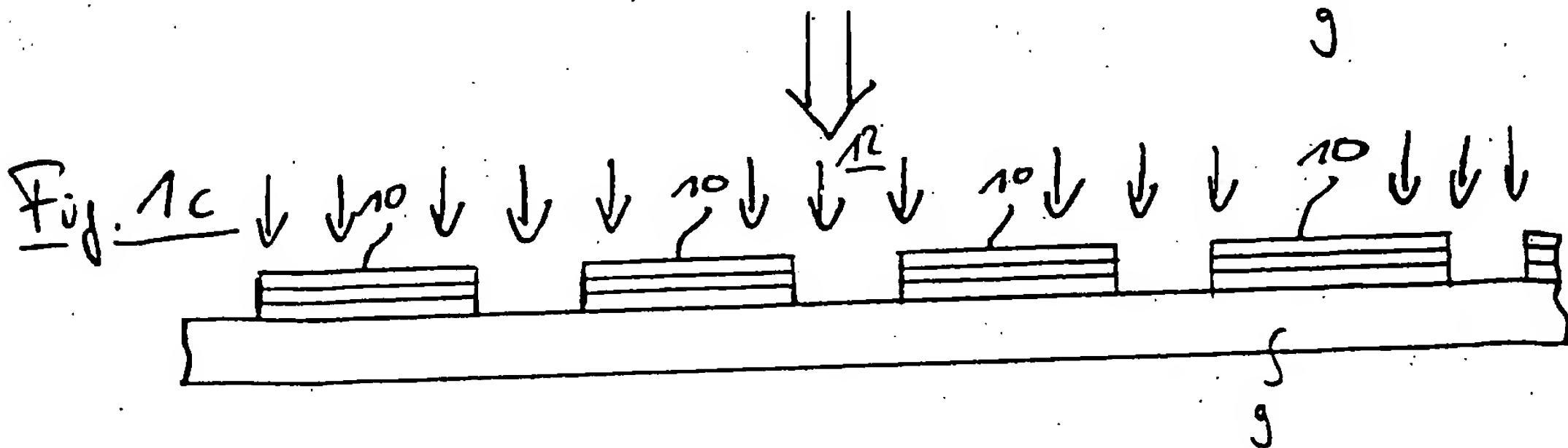
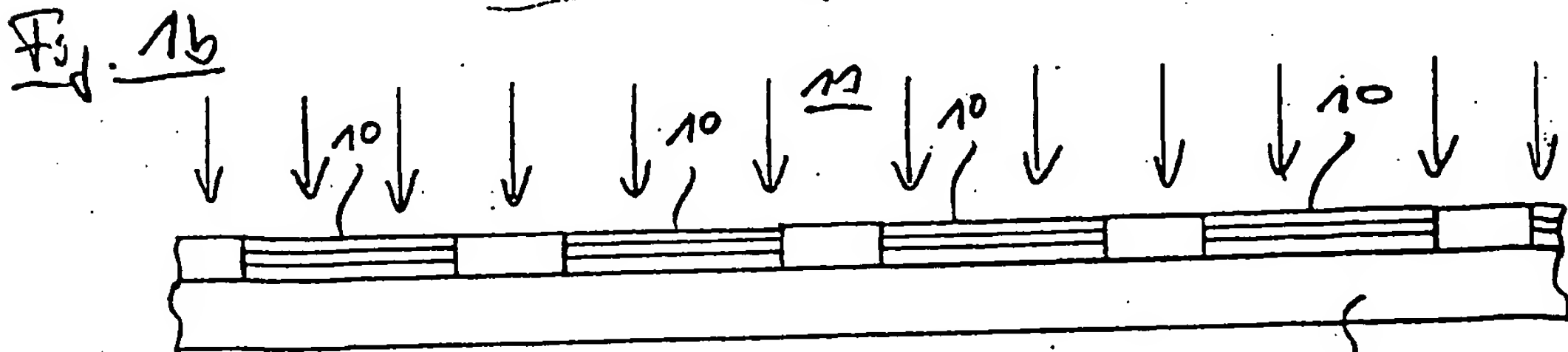


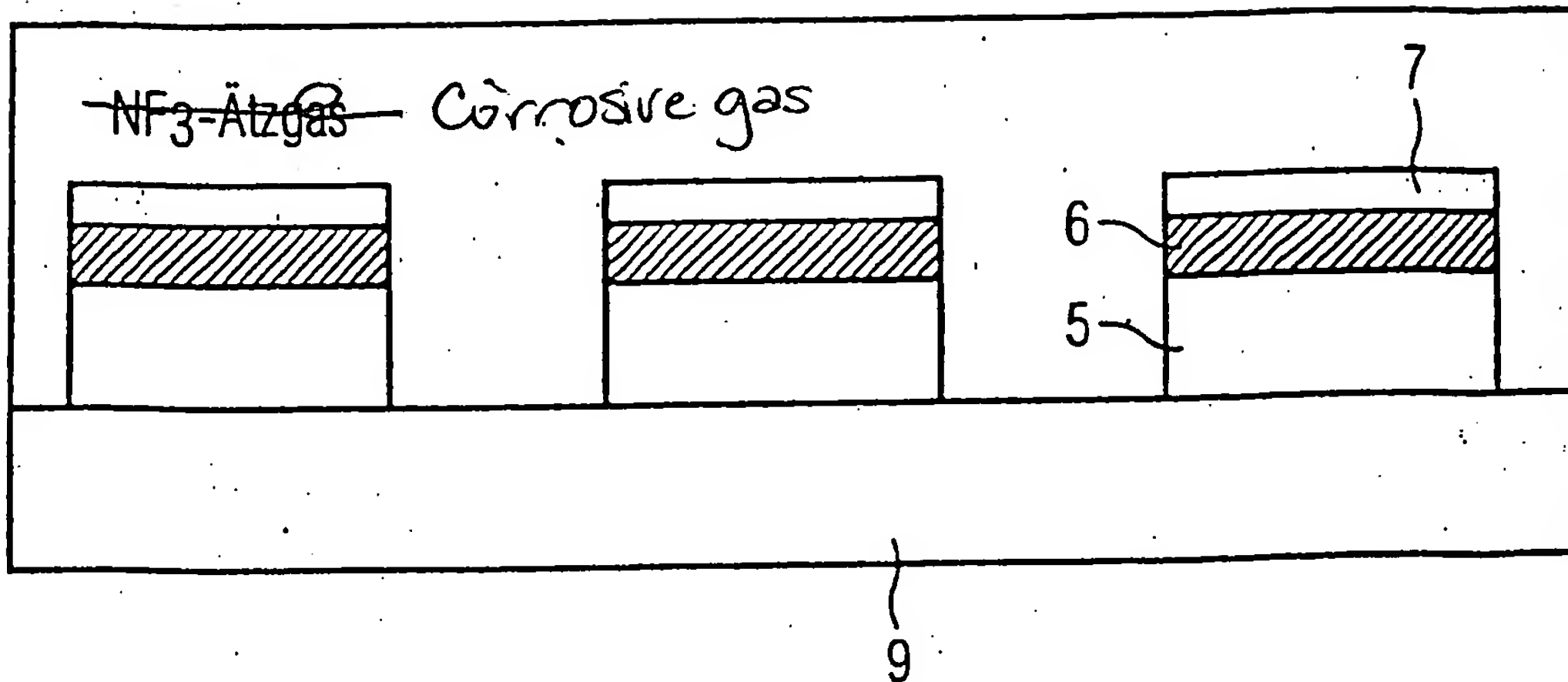
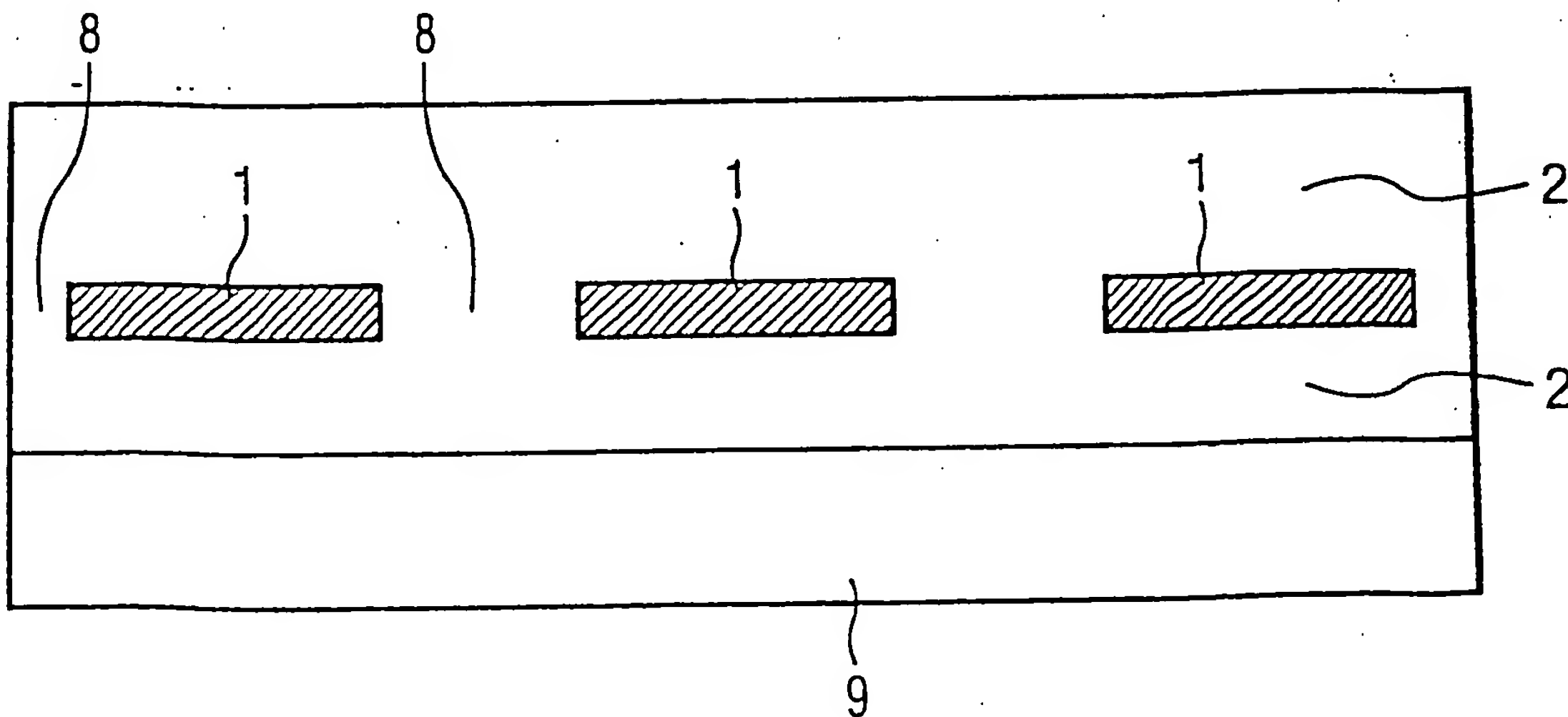
Fig. 2cFig. 2d

Fig. 3a

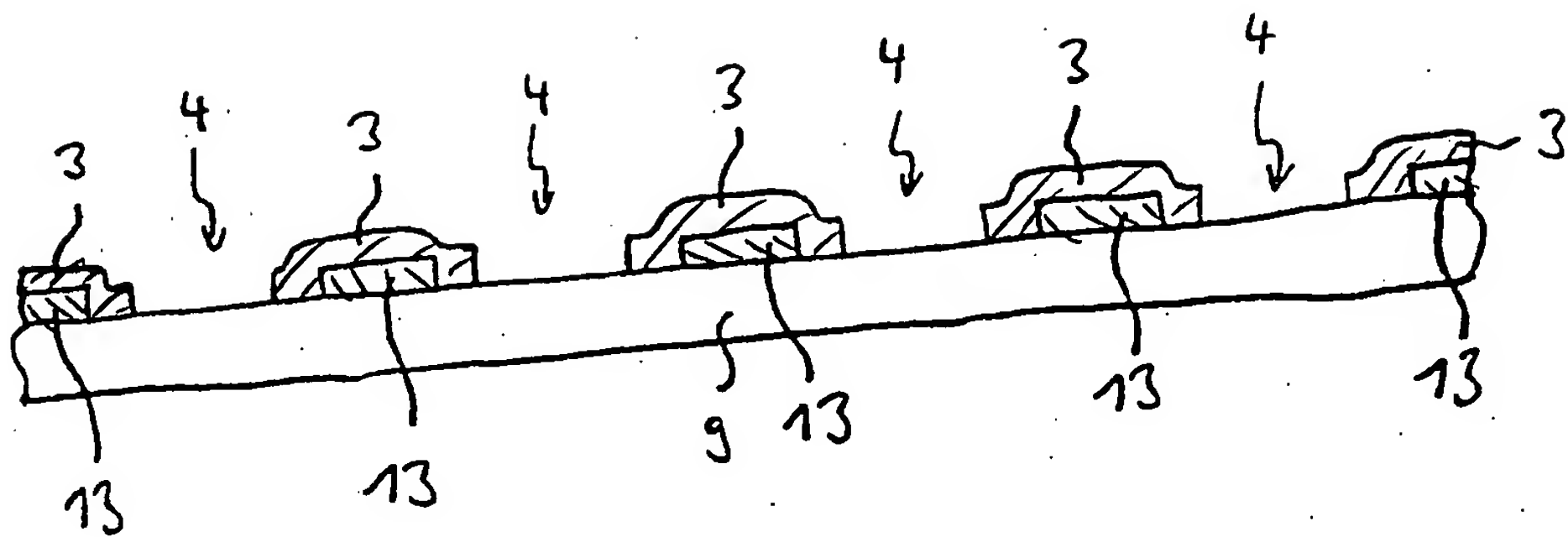


Fig. 3b

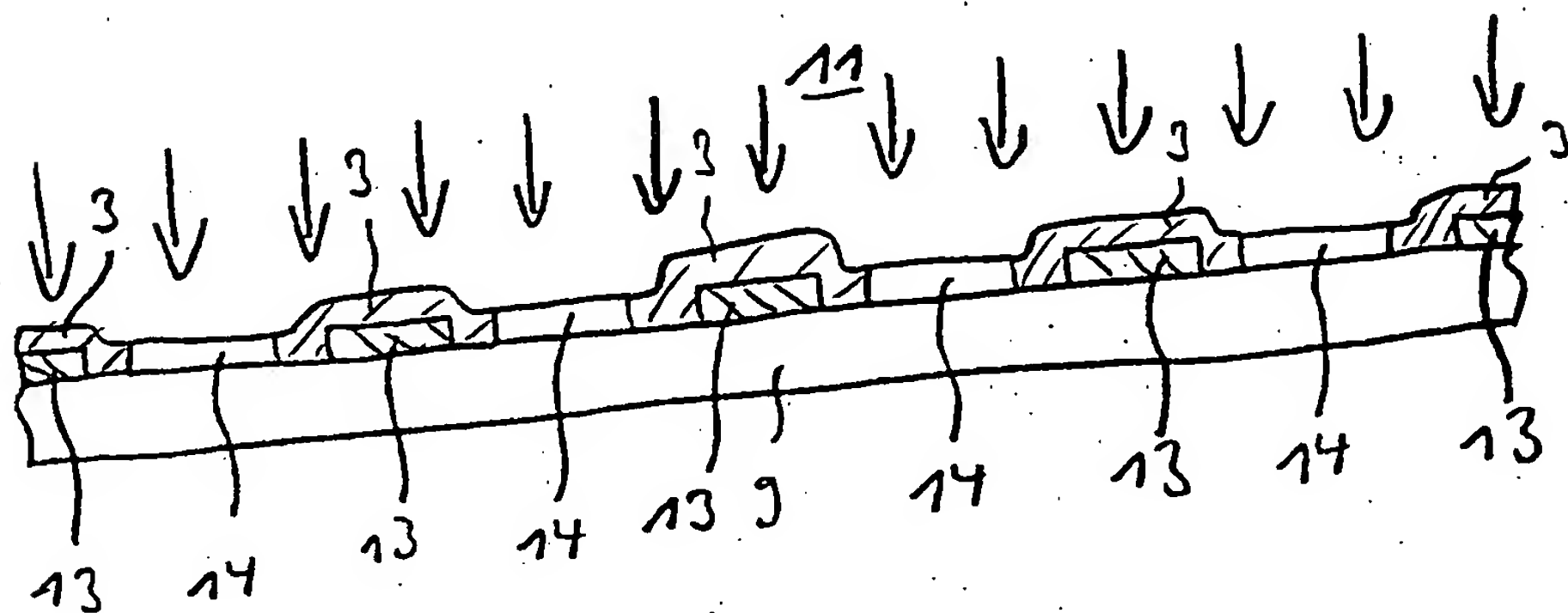
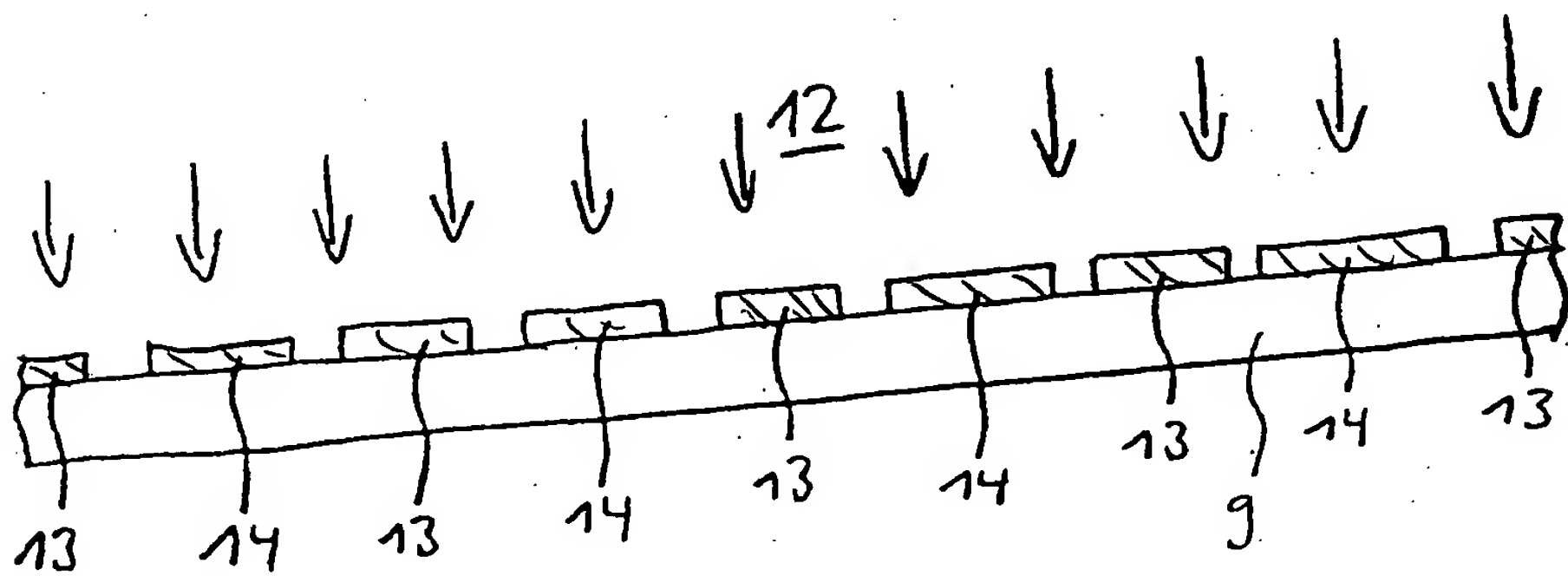


Fig. 3c



5/5

